Hysteresis in the quantum Hall regimes in electron double quantum well structures

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We present in this paper experimental results on the transport hysteresis in electron double quantum well structures. Exploring the measurement technique of xing the magnetic eld and sweeping a front gate voltage (V_g) , we are able to study the hysteresis by varying the top layer Landau level llings while maintaining a relatively constant lling factor in the bottom layer, allowing us to tackle the question of the sign of R_{xx} (up)- R_{xx} (down), where R_{xx} (up) is the magnetoresistance when V_g is swept up and R_{xx} (down) when V_g swept down. Furthermore, we observe that hysteresis is generally stronger in the even integer quantum Halle ect (IQ HE) regime than in the odd-IQ HE regime. This, we argue, is due to a larger energy gap for an even-IQ HE state, determined by the Landau level separation, than that for an odd-IQ HE state, determined by the Zeem an splitting.

There is a great deal of current interest in the study of the double quantum well $(D \ Q \ W)$ structures¹. Com – pared to a single layer of the two-dimensional electron or hole system (2D ES or 2D HS), the existence of another layer introduces signi cant interaction e ects between two quantum wells. O ver the years, many novel physical phenomena have been observed^{2,3,4,5,6,7,8,9,10}. In addition, since the distance (or the coupling) between the two quantum wells can be controllably tuned from a few tenths of nanometer to several microns, $D \ Q \ W$ structures have shown prom ise as possible future electronic devices for next generation inform ation processing¹¹.

Recently, a new phenom enon has been discovered in the DQW structures: electronic transport hysteresis^{12,13}. It was observed that, when the densities of two wells are di erent and tunneling is negligible, the magnetotransport coe cients show hysteretic behavior when the magnetic (B) eld is swept up and down. This hysteretic behavior occurs when only one QW is in the integer quantum Halle ect (IQHE) regime, and is believed to be due to a spontaneous charge transfer between the two layers¹². Speci cally, when one layer enters into an IQ HE state, its Ferm i level jum ps from one Landau level to another. Consequently, the chem ical potential between the two QW 's becom es unbalanced. In reaching an equilibrium state, a spontaneous charge transfer from one QW to the other will occur, via the ohm ic contacts. Since one QW is in the IQHE reqime where the bulk is insulating, redistribution of the transferred charges takes a nite time to reach completion. This nite time constant, combined with the nite sweeping rate of the B eld, gives rise to a hysteresis in electronic transport.

This hysteretic electronic transport was rst observed in a single, high electron mobility quantum well with a low mobility parallel conducting channel¹², and later in hole DQW structures¹³. So far, no studies have been conducted in the most common DQW structures, the electron DQW 's. Thus, questions remain whether the hysteresis is universal and occurs in electron DQW 's.

In this paper, we present experimental results of the transport hysteresis in electron DQW structures. Exploring the measurement technique of xing the magnetic eld and sweeping a front gate voltage (V_{α}) , we are

able to study the hysteresis by varying the top layer Landau level lling while maintaining a relatively constant

ling factor in the bottom layer, allowing us to tackle the question of the sign of R_{xx} (up)- R_{xx} (down), where R_{xx} (up) is the magnetoresistance when V_g is swept up and R_{xx} (down) when V_g swept down. Furtherm ore, we observe that hysteresis is generally stronger in the even-IQ HE regime than in the odd-IQ HE regime. This, we argue, is due to a larger energy gap for an even-IQ HE state, determ ined by the Landau level separation, than that for an odd-IQ HE state, determ ined by the Zeem an splitting.

The electron DQW sample (EA1025) was MBE (molecular beam epitaxy) grown. The schematic diagram of the growth structure is shown in Fig. 1 (a). The GaAs quantum well width is 20 nm. The two QW 's are separated by an A lo:3G a0:7A sbarrier of 100nm thick. Because of this large separation, the tunneling between the two wells is negligible and the symmetric-antisymmetric energy gap is virtually zero. Standard Hall structures with a Ti/Au Schottkey gate were fabricated. Ohm ic contacts were m ade by alloying Au/Ge in a form ing gas 420 C for a few m inutes. E lectron transport m eaat surem ents were perform ed in a pum ped ³H e system with a base tem perature (T) of 300 mK, using the standard low frequency (13 Hz) lock-in detection techniques. The excitation current is 20 nA. Transport hysteresis was also studied in similar DQW 's of di erent barrier thickness. It was observed in a sample of 25nm barrier thickness. In another sample of 10 nm thickness, where the tunneling between two layers is nite, no hysteresis was observed.

Fig. 1 (b) shows the results of the total resistance of two layers, R, as a function of V_g at zero B eld. As V_g is negatively biased, R rst increases. C lose to the situation where the top layer is nearly depleted, a shallow dip shows up. A fler the top layer is completely depleted, R then continuously increases as V_g is further negatively biased. This non-monotonic V_g dependence was also observed in previous studies^{14,15,16}. In Fig. 1 (c), the top layer density (n_{top}) and bottom layer density (n_{bot}) are show n as a function of V_g . The densities are obtained by perform ing the FFT analysis of the low – eld Shubnikov–

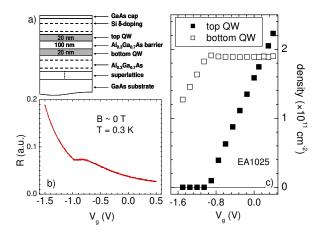


FIG.1: (a) Schem atic growth structure of sample EA1025 (b) Total resistance, R, as a function of V_g . A kink is apparent when the top layer is nearly depleted. (c) Top and bottom layers densities as a function of V_g . Electron densities are obtained from the FFT analysis of the low eld Shubnikov-de H aas oscillations.

de H ass oscillations. It is clearly seen that n_{top} decreases linearly with Vg. From the slope of this linear dependence, a distance of 450 nm between the metal gate and the center of the top layer is obtained. This value is consistent with the growth parameter of 410 nm. W hen the top layer is totally depleted, the density of bottom layer starts to decrease. The rate of decrease is slower than that of the top layer, consistent with a larger separation between the metal gate and the bottom layer.

Fig. 2a shows the magnetoresistance R_{xx} vs. B at T = 300 mK. These traces were obtained after illum inating the sample with a red light emitting diode (LED). The top layer electron density is $n_{top} = 2.2 \quad 10^{11} \text{ cm}^2$ and the bottom layer density is $n_{bot} = 2.4 \quad 10^{11} \text{ cm}^2$. The total mobility is $_{tot} = 2.4 \quad 10^6 \text{ cm}^2/\text{V}$ s. In this slightly unbalanced DQW sample, only the even IQ HE state exits^{17,18}. Consistent with previous studies^{12,13}, hysteresis is observed at these IQ HE states. In the tem – poral dependent m easurem ents (not show n), R_{xx} in the hysteretic region shows the typical exponential decay with a time constant of 1-2 m inutes¹².

Strong hysteresis is also observed when two layers are strongly in balanced, e.g., $n_{top}=n_{bot} << 1$. In Figure 2b, data were taken in the DQW sample of 25nm barrier thickness at the front gate voltage of -0.79V. At this voltage, the top layer is nearly depleted. Strong hysteresis is seen, for example, at = 1 and 2 in R_{xx} as well as in the H all resistance R_{xy} . It is interesting to notice that in the = 1 hysteretic regime, R_{xy} in the B sweeping down trace seem sto be quantized at a value close to $3h/4e^2$. At the present time, it is not clear what causes this apparent quantization. On the other hand, we note that in a recent paper Y ang proposed a W igner crystal/glass state at = 1 when the two layers are heavily in balanced¹⁹.

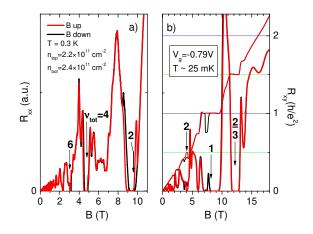


FIG.2: (a) M agnetoresistance R_{xx} and H all resistance R_{xy} in EA1025, after a brief LED illumination at 4 K.The top layer density and bottom layer density are $n_{top}=22\ 10^{11}$ cm 2 and $n_{bot}=2.4\ 10^{11}$ cm 2 , respectively. The total mobility is $_{tot}=2.4\ 10^6$ cm $^2/vs.$ Hysteresis is seen at the total lling factor =2.4 and 6. (b) M agnetotransport coe cients in a sample of 25nm barrier thickness. R_{xx} and R_{xy} for B sweeping up (red curve) and down (black curve) are taken at the xed front gate voltage of -0.79V.

It remains of interest to see whether the observed H all anomaly is related to this new phase. When < 1, no hysteresis is seen in the FQHE regime. This is consistent with the model proposed in Ref. [12]: Once < 1 is reached, the Fermi level will stay in the lowest Landau level and experience no more sudden jumps. Thus, no hysteresis is expected.

In our gated samples, the magnetotransport coe cients can be measured by xing B eld while sweeping front gate voltage (V_g). In general, as long as the Landau level lling factor is a good quantum number, sweeping B and sweeping V_q (or electron density) are equivalent. In the DQW structures, on the other hand, sweeping V_q has an extra bene t. Compared to sweeping B where both the top layer lling factor ($_{top}$) and the bottom layer lling factor (bot) change simultaneously, sweeping V_g allows us to vary top alone while maintaining a relatively xed bot. (Of course, when charge transfers between layers, bot changes slightly, causing the hysteresis.) In Fig. 3a, we show the data taken at B = 2.36T, or $_{bot} = 3.31 \{ R_{xx} (up) \text{ (for } V_q \text{ swept from } -1.5 V \text{ to }$ 0.5V) and R_{xx} (down) (for V_q swept from 0.5V to -1.5V). P ronounced hysteresis is observed at $_{top} = 1, 2, 3, and$ 4. In Fig.3b, R_{xx} (up)- R_{xx} (down) at various B elds is plotted as a function of $V_{\rm g}$. The non-zero value indicates the occurrence of hysteresis. All the traces are shifted according to their respective B eld (or bot). The four straight lines indicate the position of t_{top} as a function of V_q. It is clearly seen that hysteresis occurs only along these lines, i.e., when the top layer is in the IQ HE regime.

There are a couple of new features worthwhile em pha-

sizing in Fig. 3b. First, R_{xx} (up)- R_{xx} (down) can be either negative or positive. As indicated in Fig. 3b, the sign depends on bot: It is positive when bot is $[]_{bot} +$, and negative when $[]_{bot} = []_{bot}$, where the square brackets denote the closest integer values to and < 0:5. Second, while hysteresis only occurs when the top layer is in the IQ HE regime, that the top layer is in the IQHE regime doesn't mean that a hysteretic electronic transport will always occur. It is also related to bot. In Fig. 4, we plot R_{xx} (up) and R_{xx} (down) at three selective B eld. At B = 3.65 T (or _{bot} = 2.14), no hysteresis occurs in the entire gate voltage range at the experimental temperature of 0.3K. At B = 2:36 T (or bot= 3.31), hysteresis is seen at every IQ HE state. At an even smaller B eld, B = 1.50 T (or $_{bot} = 5.20$), the situation is more interesting: Hysteresis only occurs at the even IQHE states.

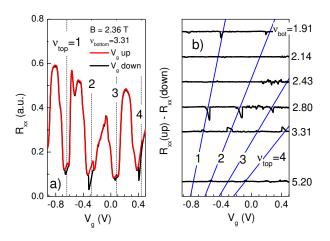


FIG.3: (a) R_{xx} as a function of the front gate voltage. The black curve R_{xx} (down)] is for V_g sweeping down from 0.5V to -1.5V and the red curve R_{xx} (up)] for V_g sweeping up from -1.5V to 0.5V. (b) R_{xx} (up) $-R_{xx}$ (down) as a function of V_g . Traces are shifted vertically according to their B eld values. The straight lines show the V_g dependence of $_{top} = 1, 2, 3$, and 4, respectively. bot is also marked for each trace.

O ur experim ental results clearly show the transport hysteresis in the electron DQW structures. Furtherm ore, the hysteretic behavior is discernable at tem peratures as high as 600 mK, much higher than the highest tem – perature (250 mK) where hysteresis was previously recorded¹³. This is due to a larger electron density and a sm aller electron e ectivem ass (m) in our electron DQW than in the hole DQW. These two factors jointly result in a larger Landau level separation at the sam e n. C onsequently, the IQHE state and hysteresis can survive at higher tem peratures.

That the sign of R_{xx} (up) $-R_{xx}$ (down) can be either positive or negative has also been observed in previous studies^{12,13} when B was varied. So far no systematic study has been conducted on this matter. In our mea-

surem ents, where B is xed and Vg varied, it is apparent that at small B elds the sign shows a system atic dependence on bot: It is positive when bot = [bot +and negative when $bot = []_{bot}$. In the following, we shall show that this dependence can be explained in a simple model. First, let us assume that the bottom layer is at the Landau level lling $[]_{bot} + . W hen_{top}$ (or V_q) is, for instance, decreased from $[]_{top} + to []_{top}$ (is positive and < 0:5), the Ferm i level jum ps down. In order to reach an equilibrium state in chem icalpotential between two layers, some electrons will move from the bottom ${\tt Q}\,{\tt W}\,$ to the top ${\tt Q}\,{\tt W}\,$. In other words, the electron density of the bottom QW decreases. Consequently, its lling factor becomes smaller and is more close to $[b_{ot}$. As a result, the resistance of the bottom QW is reduced. This, in turn, causes a reduction in R_{xx} , the total resistance of the two layers. On the other hand, when V_{α} is swept up and top increases from []topto []_{top}, the Ferm i level jum ps up. Consequently, electrons will move from the top layer to the bottom layer. Thus, bot increases and becomes closer to [l_{out} + 1/2. Since the magneto resistance generally displays a peak at half-llings, the bottom layer resistance increases, resulting in an overall increase in R_{xx} . Together, when bot = [bot + , apositive R_{xx} (up)- R_{xx} (down) is the resulting e ect. The sam e argum ent explains why the R $_{\rm xx}$ (up)-R $_{\rm xx}$ (down) is negative when $bot = []_{bot}$

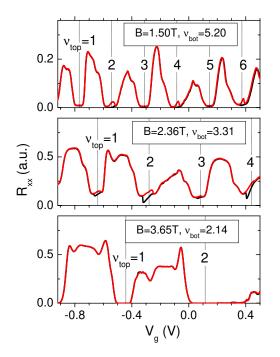


FIG. 4: R_{xx} traces at three selective B elds. The dotted lines show the V_g positions of the Landau level llings of the top quantum well.

A nother interesting observation can be made in Fig. 4:

In general, hystersis is stronger in the even IQ HE regime than in the odd-IQ HE regime. This seems to suggest that electron spin m ay also play a role. We recall that the strength of hysteresis is related to the energy gap of an IQ HE state. It is known that the energy gap of an even IQ HE state is determ ined by the Landau level separation, while the odd IQ HE state by the Zeem an splitting. Since the e ective g-factor for G aAs is jrj=0.44, the Landau level separation (h! c = heB =m 20 B [T] K elvin) is m uch larger than the Zeem an splitting ($jrj_B B 0.3$

B [I] K elvin). This explains why in Fig. 4 the hystersis in the even IQ HE regime is stronger than that in the odd IQ HE regime.

In sum m ary, in this paper we present experim ental results on transport hysteresis e ects in electron double quantum well structures. The hysteresis is studied by varying the top layer Landau level lling while m aintaining a relatively constant lling factor in the bottom layer. This measurem enthas allow ed us to identify that the sign of R_{xx} (up)- R_{xx} (down) is positive when $_{bot} = [b_{ot} + and negative when <math>_{bot} = [b_{ot} + and negative when <math>_{bot} = [b_{ot} + and negative when bot = 0.5$. A simple model is proposed to understand this sign dependence. Furtherm ore, it is observed that hysteresis is generally stronger in the even-

IQ HE regime than in the odd-IQ HE regime. This, we argue, is due to a larger energy gap for an even-IQ HE state, determ ined by the Landau level separation, than that for an odd-IQ HE state, determ ined by the Zeem an splitting.

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